

L Number	Hits	Search Text	DB	Time stamp
1	22	((dose or dosing or dosage or intensity) same (second adj (mask or photomask or reticle))) not ((430/5,311-312,319,394,396 or 355/53,77 or 378/34-35 or 716/19-21).cc1s. and (phase adj shift\$3 same (mask or photomask or reticle)) same (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) not (((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherent\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4)))) and (resist or photoresist) and phase adj shift\$3 same (mask or photomask or reticle)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:01
2	9	((full adj phase adj shift\$3 or full adj phase) adj (mask or reticle or photomask)) not (((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist)) and 430/5.cc1s.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:03
3	7	((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist)) and 430/5.cc1s.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:04
4	525	((430/5,311-312,319,394,396 or 355/53,77 or 378/34-35 or 716/19-21).cc1s. and (phase adj shift\$3 same (mask or photomask or reticle)) same (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) not (((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherent\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:05

5	46	(((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) not ((((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) and (dose or dosage or intensity))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:07
6	102	(((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) and (dose or dosage or intensity))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:07
-	1815	(phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/30 14:30
-	798	((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:37
-	126	(((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:25
-	97	(((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:25

-	89	(((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr\$nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:26
-	65	(((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr\$nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) and (dose or dosage or intensity)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/13 11:14
-	24	(((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr\$nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) not (((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr\$nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) and (dose or dosage or intensity)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/13 11:15
-	2	((("20020187636") or ("20020197543")).PN.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:33
-	22	((("6284419") or ("6519501") or ("20020076622") or ("6453457") or ("6337172") or ("6541165") or ("6503666") or ("6162568") or ("6255024") or ("6268091") or ("6319644") or ("6421111") or ("5972569") or ("5405721") or ("6042973") or ("6127096") or ("6374396") or ("6096457") or ("6106979") or ("6040892") or ("6120952") or ("5741624")).PN.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:34

-	21	((("20020187636") or ("20020197543").PN.) or ((("6284419") or ("6519501") or ("20020076622") or ("6453457") or ("6337172") or ("6541165") or ("6503666") or ("6162568") or ("6255024") or ("6268091") or ("6319644") or ("6421111") or ("5972569") or ("5405721") or ("6042973") or ("6127096") or ("6374396") or ("6096457") or ("6106979") or ("6040892") or ("6120952") or ("5741624").PN.) not (((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or (mask or photomask or reticle) near\$3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near\$3 gate or gate adj shr\$nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherent\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4)))	USPAT; US-PGPUB	2003/04/28 16:35
-	398	((430/5,311-312,319,394,396 or 355/53,77 or 378/34-35 or 716/19-21).ccis. and (phase adj shift\$3 same (mask or photomask or reticle)) same (trim or (mask or photomask or reticle) near\$3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) not (((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or (mask or photomask or reticle) near\$3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near\$3 gate or gate adj shr\$nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherent\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/13 11:17
-	4	((("5885734") or ("6077630") or ("20010000240") or ("20010028985").PN. ("4037918") or ("4456371") or ("5302477") or ("5308741") or ("5316878") or ("5324600") or ("5328807") or ("5334542") or ("5352550") or ("5364716") or ("5424154") or ("5480746") or ("5496666") or ("5498579") or ("5503951") or ("5523186") or ("5527645") or ("5532090") or ("5537648") or ("5538815") or ("5539568") or ("5565286") or ("5573890") or ("5595843") or ("5620816") or ("5635316") or ("5636131") or ("5702848") or ("5725969") or ("5761075") or ("5766804") or ("5766806") or ("5807649") or ("5827623") or ("5858580") or ("5885734") or ("5923566") or ("5994002") or ("5998068") or ("6004702") or ("6010807") or ("6057063") or ("6066180") or ("6077630") or ("6083275") or ("6228539") or ("6251549") or ("6258493").PN.	USPAT; US-PGPUB USPAT; US-PGPUB	2003/04/28 18:09 2003/04/30 14:58
-	9	((("5472814") or ("5923562") or ("6130012") or ("6139994") or ("6185727") or ("6335128") or ("6338922") or ("20010000240") or ("20010028985").PN.	USPAT; US-PGPUB	2003/04/30 15:02

-	12	((("6420074") or ("6436590") or ("20020083410") or ("20020122994") or ("20020127479") or ("20020129327") or ("20020136964") or ("20020142231") or ("20020142232") or ("20020144232") or ("20020152454") or ("20020155363"))).PN.	USPAT; US-PGPUB	2003/04/30 15:06
-	6	((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist)) and 430/5.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/13 11:17
-	1	("6524752").PN.	USPAT; US-PGPUB	2003/05/08 16:46
-	4	((full adj phase adj shift\$3 or full adj phase) adj (mask or reticle or photomask)) not (((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist)) and 430/5.ccls.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/02/13 11:18
-	357	((dose or dosing or dosage or intensity) same (second adj (mask or photomask or reticle)) not (((430/5,311-312,319,394,396 or 355/53,77 or 378/34-35 or 716/19-21).ccls. and (phase adj shift\$3 same (mask or photomask or reticle)) same (trim or (mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) not (((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or (mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr\$nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/05/13 18:49
-	16	((dose or dosing or dosage or intensity) same (second adj (mask or photomask or reticle)) not (((430/5,311-312,319,394,396 or 355/53,77 or 378/34-35 or 716/19-21).ccls. and (phase adj shift\$3 same (mask or photomask or reticle)) same (trim or (mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) not (((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or (mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr\$nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4)))) and (resist or photoresist) and phase adj shift\$3 same (mask or photomask or reticle)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:09

-	92	(((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) and (dose or dosage or intensity)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:07
-	37	(((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) not (((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4))) and (dose or dosage or intensity)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:06
-	495	((430/5,311-312,319,394,396 or 355/53,77 or 378/34-35 or 716/19-21).ccls. and (phase adj shift\$3 same (mask or photomask or reticle)) same (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) not (((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim or ((mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$5)) and (transistor near3 gate or gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradiat\$4 or light or illumina\$4)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:04
-	7	((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist)) and 430/5.ccls.	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:03
-	8	((full adj phase adj shift\$3 or full adj phase) adj (mask or reticle or photomask)) not (((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist)) and 430/5.ccls.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:03

-	20	<p> {{{dose or dosing or dosage or intensity}  same (second adj (mask or photomask or  reticle))) not  (((430/5,311-312,319,394,396 or 355/53,77  or 378/34-35 or 716/19-21).cccls. and  (phase adj shift\$3 same (mask or photomask  or reticle)) same (trim or ((mask or  photomask or reticle) near3 set) or  (second or complementary) adj (mask or  photomask or reticle) or overla\$5)) not  ((((phase adj shift\$3 same (mask or  photomask or reticle)) same (resist or  photoresist or photosensit\$4)) and (trim  or ((mask or photomask or reticle) near3  set) or (second or complementary) adj  (mask or photomask or reticle) or  overla\$5)) and (transistor near3 gate or  gate adj shr?nk\$3)) and (resolution or  resolv\$3)) and (optical adj (parameter or  configurat\$3) or aperture or (wavelength  or coherenc\$1 or illumina\$4 or focus or  defocus) same (expos\$3 or radia\$4 or  irradia\$4 or light or illumina\$4)))) and  (resist or photoresist) and phase adj  shift\$3 same (mask or photomask or  reticle) </p>	USPAT; US-PGPUB; EPO: JPO; IBM_TDB	2004/05/21 10:00
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